

MICROFABRICATION

Wet bench

Manufacturer: Puerstinger High Purity Systems GmbH



General Description:

The cleanroom is equipped with 3 wet-benches for solvent, acid and base processes. The tanks have the capacity of 5 wafers of 8". The solvent bench is mainly dedicated to lift-off processes and is equipped with an ultrasonic bath with 8" substrate capability. The base bench is dedicated to KOH silicon etching and base-based metallic etching solutions. The acid bench is dedicated to wafer cleaning and acid-based thin layers etching solutions.

Key Specifications:

- Solvent, acid and base manual wet-benches
- Cleaning, removing and etching purpose
- Up to 4 Acid tanks, 5x8 inches
- KOH silicon etching
- Ultrasonic bath for lift-off processes
- Miscellaneous chemical processes

Availability	Use allowed for all researchers with permission
Location	Cleanroom C5 Europastraße 12 9524 Villach
Responsibles / Contact	Dr. Sarah Risquez Tel.:+43 4242 56300 275